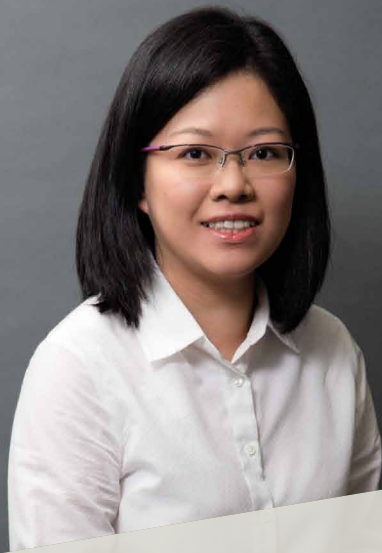


Lo Wen Yu

B.Eng. (Elect.) (Hons)., MIP
Associate Director
Registered Patent Attorney (Singapore)

Direct: +65 6303 6227
Email: lo.wenyu@amicallaw.com



Lo Wen Yu is an Associate Director of Amica Law LLC, and a registered patent attorney in Singapore. Her practice focuses on patent aspects of intellectual property.

Wen Yu has substantial experience in working with clients in diverse industries such as electronics, communications, telecommunications, semiconductor, offshore and marine technology, electrical and mechanical engineering.

Wen Yu graduated from the National University of Singapore with a Bachelor of Engineering (Electrical) (Honours) in 2000, completed a Graduate Certificate course in Intellectual Property Law in 2001, and graduated with a degree in Master of Intellectual Property from Franklin Pierce Law Center, USA in 2004. Wen Yu qualified as a registered patent attorney in Singapore in 2006 and is a member of the pioneer group of locally qualified patent attorneys in Singapore.

Before joining Amica Law LLC, Wen Yu was an in-house associate at a multinational corporation focussing on patent protection and management, and a patent practitioner at a leading Singapore law firm.

Experience

Her work encompasses various aspects of patent practice, including:

- drafting and prosecuting patent applications in Singapore and worldwide;
- conducting patent searches and advising on patentability of inventions;
- advising on patent filing and procurement strategies;
- managing patent portfolios and patenting activities in various countries;
- preparing opinions on patent infringement and validity, and freedom-to-operate.

Memberships

Wen Yu is a member of the Examination Committee which is appointed to set and mark qualifying examination papers for the Singapore Patent Agents Qualifying Examination. She is also a member of the Association of Singapore Patent Attorneys (ASPA) and the American Intellectual Property Law Association (AIPLA).

Key Practice Areas

- Information Technology
- Patent & Design Protection